

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Park et al.

Confirmation No.: 5520

Serial No.: 10/828,596

Group Art Unit: 2811

Filed: April 21, 2004

Examiner: Ori Nadav

For: METHODS OF FORMING METAL THIN FILMS, LANTHANUM OXIDE FILMS
AND HIGH DIELECTRIC FILMS FOR SEMICONDUCTOR DEVICES USING
ATOMIC LAYER DEPOSITION

Date: May 2, 2008

Mail Stop Amendment
Commissioner for Patents
Box 1450
Alexandria, VA 22313-1450

**RESPONSE TO OFFICE ACTION
DATED FEBRUARY 11, 2008**

Sir:

The present Response is being filed to address the issues raised in the Office Action mailed February 11, 2008.

It is not believed that an extension of time and/or additional fee(s)-including fees for net addition of claims-are required, beyond those that may otherwise be provided for in documents accompanying this paper. In the event, however, that an extension of time is necessary to allow consideration of this paper, such an extension is hereby petitioned under 37 C.F.R. §1.136(a). Any additional fees believed to be due in connection with this paper may be charged to our Deposit Account No. 50-0220.

Listing of claims begins on Page 2 of this paper.

Remarks begin on Page 12 of this paper.